

[charged-particle-excluding means is] the electrodes, which are disposed so as to interpose a plasma flow spurted out from the plasma vent therebetween, are provided in and between the vicinity of said plasma vent and the vicinity of said substrate supporting table.

2. A surface treatment apparatus [according to claim 1, wherein high-frequency electric power is inputted to said plasma generating electrodes] for generating plasma by plasma generating electrodes in a casing having plasma generating electrodes, a raw-gas inlet and a substrate supporting table, plasma ionizing the raw gas and plasma processing a surface of said substrate, which is mounted on said substrate supporting table; characterized in that

said casing is partitioned to two chambers, that is, a plasma generating chamber provided with said plasma generating electrodes and a substrate processing chamber provided with said substrate supporting table;

said substrate processing chamber communicates with said plasma generating chamber through at least one plasma vent; and

a magnetic field, in which a line of magnetic force acts in a direction orthogonal to a plasma flow, is provided in at least a part between the vicinity of said plasma vent and the vicinity of said substrate supporting table.

3. A surface treatment apparatus [according to claim 1 or claim 2, wherein said charged-particle-excluding means is disposed so as to cross said plasma and comprises a conductive member having at least one plasma passing hole, to which voltage is applied] for generating plasma by plasma generating electrodes in a casing having plasma generating electrodes, a raw-gas inlet and a substrate supporting table, plasma ionizing the raw gas and plasma processing a surface of said substrate, which is mounted on said substrate supporting table; characterized in that

said casing is partitioned to two chambers, that is, a plasma generating chamber provided with said plasma generating electrodes and a substrate processing chamber provided with said substrate supporting table;

said substrate processing chamber communicates with said plasma generating chamber through at least one plasma vent; and

a conductive member, to which electric voltage is applied, is provided at a part of said plasma vent.

Please amend Claim 5 as follows:

5. A surface treatment apparatus according to [claim 1 or claim 2, wherein said charged-particle-excluding means comprises a pair of electrodes that are disposed so as to interpose plasma flow, which is spurted from said plasma vent, therebetween] any one of

Claims 1 to 3, wherein high frequency electric power is inputted to said plasma generating electrodes.

Please delete Claim 6 without prejudice or disclaimer.

Please amend Claims 7-12 as follows:

7. A surface treatment apparatus according to any one of claims 1 to [6] 3, wherein said plasma vent has a required orifice shape or a nozzle shape.

8. A surface treatment apparatus according to any one of claims 1 to [7] 3, wherein said raw-gas inlet defines an opening on a side face of said plasma vent.

9. A surface treatment apparatus according to claim [3 or claim 6, wherein said charged-particle-excluding means constitutes a part of said plasma vent] 2, wherein said magnetic field is provided at said plasma vent.

10. A surface treatment apparatus according to [claim 1] any one of claims 1 to 3, wherein said plasma vent has a circular section.

11. A surface treatment apparatus according to [claim 1] any one of claims 1 to 3, wherein said plasma vent has a slit shape.

12. A surface treatment apparatus according to [claim 1] any one of claims 1 to 3, wherein said substrate is given with electric potential.

#### **IN THE DRAWINGS**

Please amend the drawings as follows:

Please delete Fig. 1 without prejudice.

Please amend Fig. 2 per the attached copy of Fig. 2 marked in red ink which adds reference numerals 3a and 3b.

#### **REMARKS**

This Preliminary Amendment is made for entry into the national stage from the international PCT application prior to examination in the United States Patent Office. This Amendment is made for clarification purposes and not for reasons related to patentability under Title 35 of the United States code.